

WHAT IS CLAIMED IS:

1. A method of fabricating a thin-film magnetic head comprising the steps of:

forming a lower pole having a substantially flat upper surface,

forming a non-magnetic layer on said upper surface of said lower pole,

forming a magnetic block on said non-magnetic layer,

etching at least said non-magnetic layer using said magnetic block as a mask to form between said lower pole and said magnetic block a gap layer having substantially the same width as the width of said magnetic block,

forming an insulation layer in a predetermined thickness on said lower pole so as to cover said gap layer and said magnetic block,

polishing said insulation layer and said magnetic block using an upper surface of said insulation layer corresponding to an edge portion of said lower pole as a polishing stop surface to form an upper sub-pole, and

forming on said upper sub-pole an upper pole wider than said upper sub-pole.

2. A method as set forth in claim 1, further comprising the step of forming around said lower pole a polishing stop pattern for providing said polishing stop

surface.

3. A method as set forth in claim 2, wherein said polishing stop pattern comprises a plurality of patterns.

4. A method as set forth in claim 2, wherein said polishing stop pattern provides a terminal for connecting said thin-film magnetic head to an external circuit.

5. A method as set forth in claim 1, wherein said step of forming said gap layer includes the step of etching a part of said lower pole using said magnetic block and said gap layer as a mask, whereby a lower sub-pole is formed as one body with said lower pole.

6. A method as set forth in claim 1, further comprising the step of forming a magneto-resistance effect element on a lower shield, wherein said lower pole is provided as an upper shield opposed to said lower shield with said magneto-resistance effect element therebetween.

7. A thin-film magnetic head fabricated by the method as set forth in claim 1.